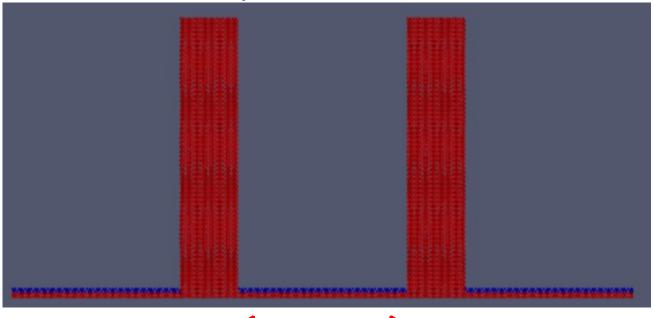
Special Topics on Basic EECS I Design Technology Co-Optimization Lecture 13

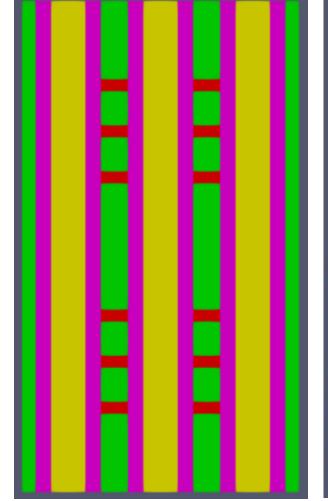
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Gwangju Institute of Science and Technology (GIST)

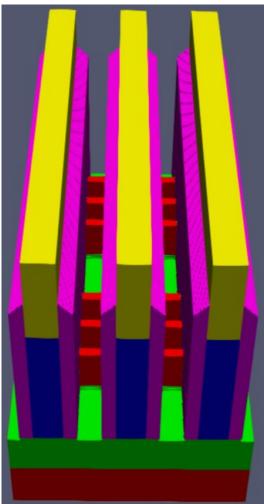
L13

Coming back to the FinFET

- There are fins.
 - -Separated by 20 nm
 - Test a two-fin structure. (32-nm-tall)





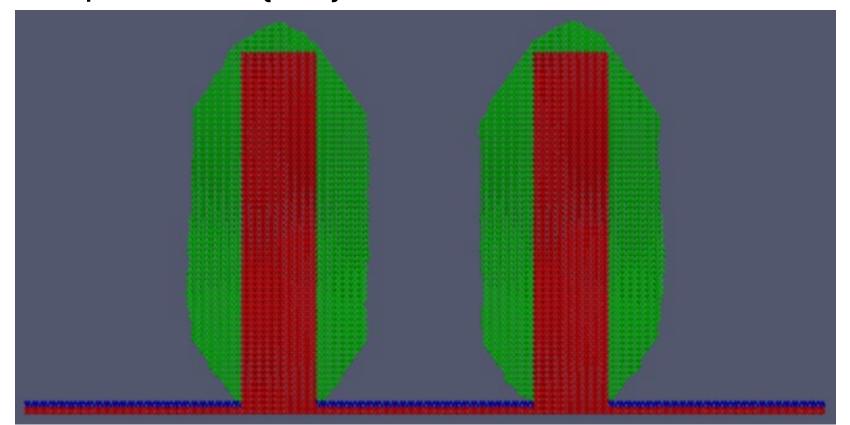


20 nm

GIST Lecture

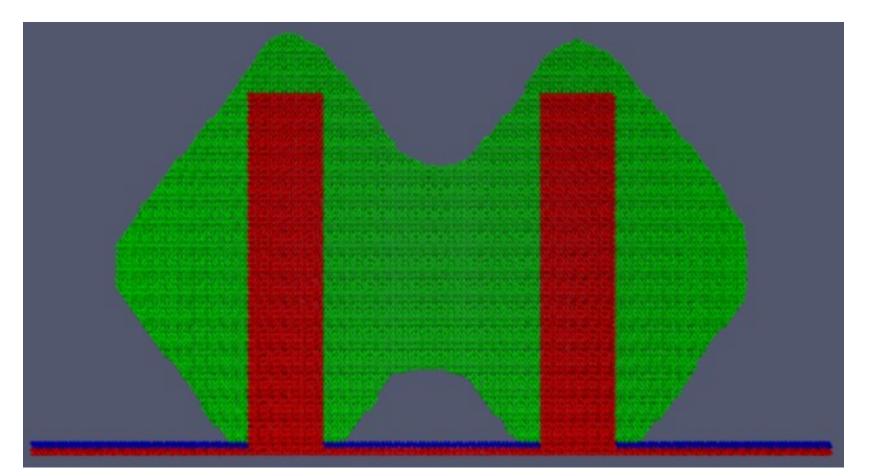
Thickness ~ 4.5 nm

- They are separated.
 - -{111} surfaces are observed.
 - -On the top surface, {311} surfaces are dominant.



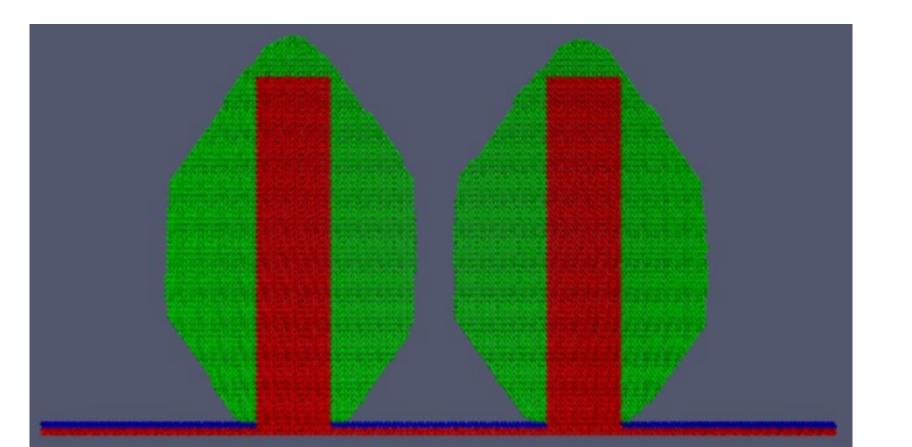
Double the number of atoms.

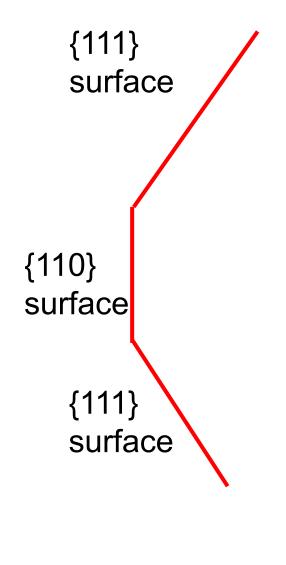
- They are bridged. It looks like mushrooms.
 - -(Can we trust this result?)



In between,

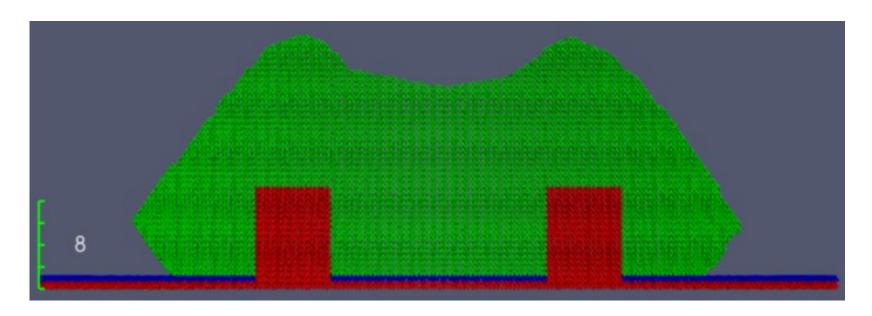
- We can find a condition of unmerged fins.
 - The fin shape can be well approximated.





Impact of fin height

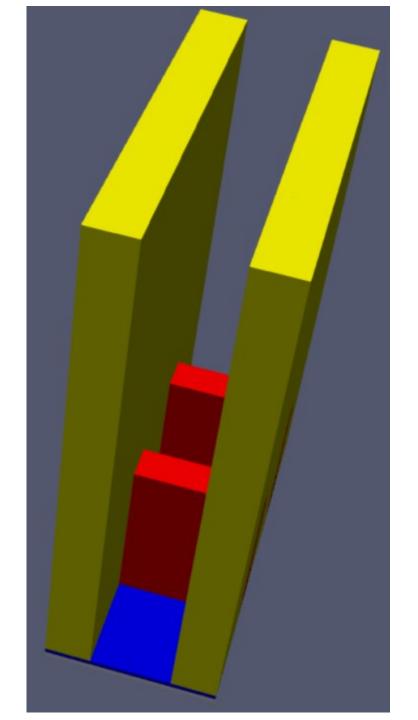
- Consider 8-nm-tall fins.
 - Repeat the previous test. (The same number of atoms in the last slide)



Try this.

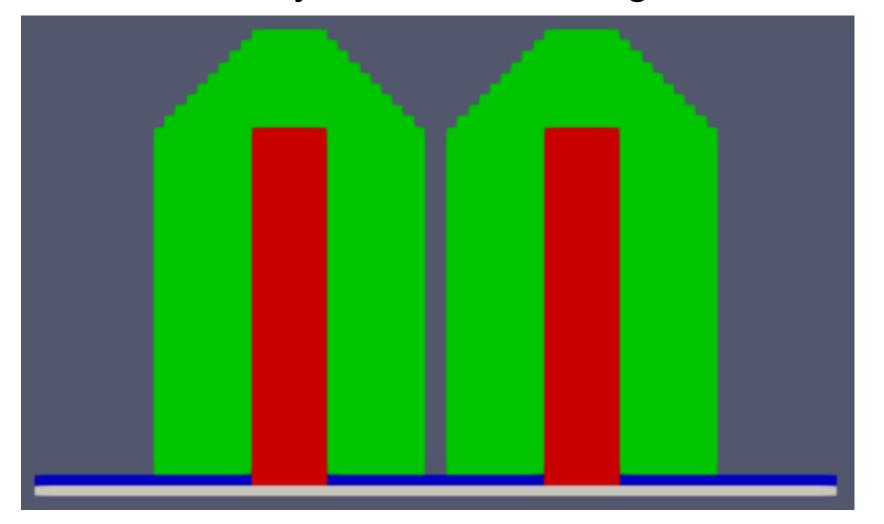
- Construct a test structure.
 - -34 nm (= 9 +16 + 9) by 74 nm (= 20 + 7 + 20 + 7 + 20)
 - -(The colors of the regions do not matter.)
 - Now, we are ready to test the selective epitaxial growth.

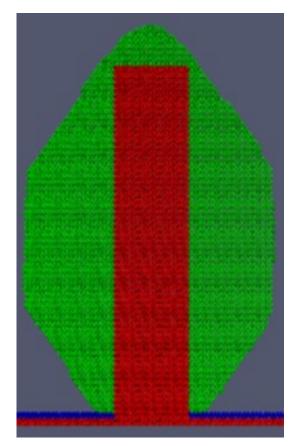
```
model (name="model_sd") {
    select (region="Fin")
    select (region="SD")
}
```



Isotropic depo with a thickness of 9 nm

No boundary condition. 45 degree.





New growth statement

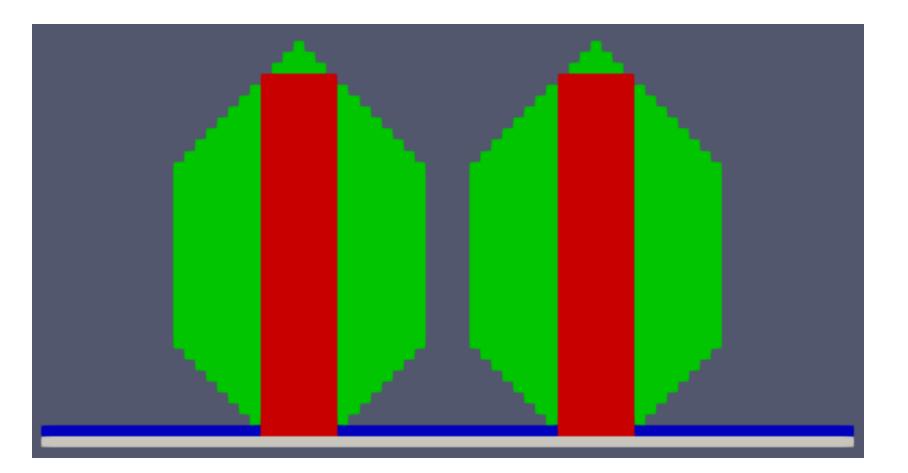
- This new statement takes three spec arguments.
 - -Name of the added region: region
 - -Name of the material selectivity: model
 - -(Minimum) number of voxels to be added: number

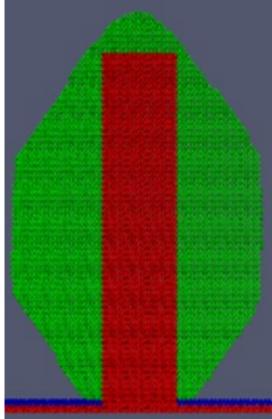
```
growth (region="SD", model="model_sd", number=12000)
```

- -DO NOT increase number too aggressively.
- Main idea
 - -Check the existing surfaces.
 - -{111} surfaces are approximated as diagonal surfaces. (45°)

When the number of voxels is 12000,

- We have a similar profile.
 - -Of course, details cannot be reproduced.

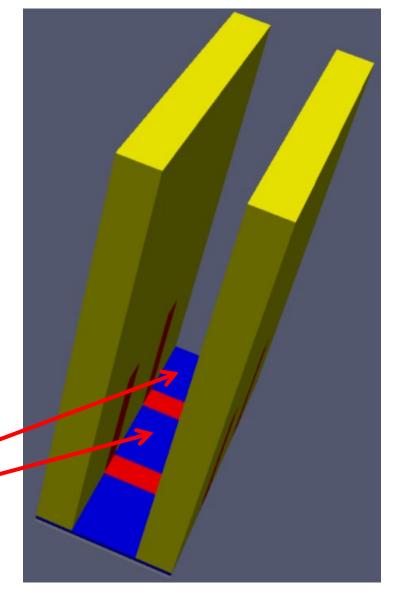




Three-dimensional shape

- Cavity etching
 - The 32-nm-tall fin is etched anisotropically.
 - The fin underneath the spacer is not etched. → In reality, these parts are also etched.
 - Etch depth is equal to the fin height. → In reality, it is not.

There is no fin.



Growth after cavity etching

Contribution from two channels is dominant.

-In this example, increased number introduces more voxels to

make a diamond-like shape.

model (name="model sd") {

select (region="Fin")

neighbor (region="Spacer")

select (region="SD")

GIST Lecture

Homework#13

- Due: 08:00 on Nov. 3
- Submit a report through the GIST LMS system.
 - -Construct the simple structure used in the L13 lecture material. Then, by using a growth statement, grow the epitaxial layer.

GIST Lecture 14

Thank you!